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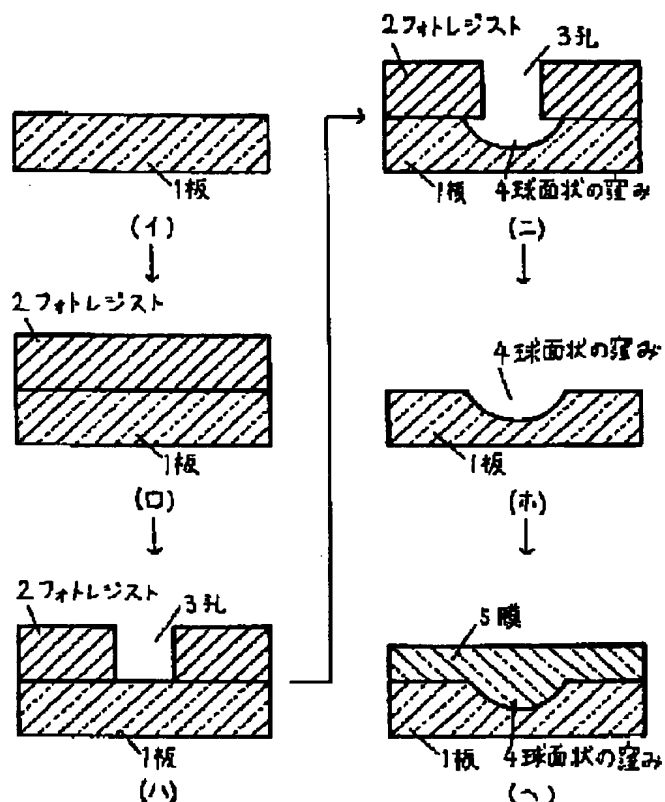
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APPLICANT : ISHIDA KOICHI;

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TITLE : MICROLENS FORMED BY ISOTROPIC ETCHING



ABSTRACT : PURPOSE: To develop a microlens, simple in manufacturing, profitable in mass production and never have been developed conventionally, by employing thin film forming technique, photo-lithograph and isotropic etching technique.

CONSTITUTION: A spherical recess 4, produced by the isotropic etching of a plate 1, is filled with a film 5, made of a substance having a large refractive index of light. whereby the film 5 functions as a lens. The microlens, having a diameter smaller than $1\mu\text{m}$, can be formed by a technique employed for the manufacture of a semiconductor integrated circuit.

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